

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE

(Rev.2-32) PATENT AND TRADEMARK OFFICE  
INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT  
(Use several sheets if necessary)

Atty Docket: ADACHI P163USP2

Examiner: John J. Mann

Group: 1731

Applicant: Akira IKUSHIMA, Kazuya SAITO, Takashi  
MIURA and Shogo NASUDA

## U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Sub- Class	Class	Filing Date, if Appropriate
	4,028,080	Jun. 1977	Di Vita	-	-	
	4,157,253	Jun. 1979	Hernandez	-	-	
	4,182,664	Jan. 1980	Maklad	-	-	
	5,267,343	Nov. 1993	Lyons	-	-	
	5,620,496	Apr. 1997	Erdogan	-	-	
	5,983,673	Nov. 1999	Urano	-	-	
	6,058,739	May 2000	Morton	-	-	
	5,478,371	Dec. 26, 1995	Lemaire et al	-	-	

## FOREIGN PATENT DOCUMENTS

Examiner Initials	Document Number	Date	Country	Sub- Class	Class	Translation Yes No
	0 687 924 A1	Dec. 20, 1995	EPO	-	-	
	2808457	Aug. 1974	Germany	-	-	
	4-342427		Japan	-	-	
	4-342436		Japan	-	-	
	6-199539	Jun. 7, 1994	Japan	-	-	
	52-94657	Nov. 1993	Japan	-	-	
	54-134721	Oct. 1979	Japan	-	-	
	57-188423	Nov. 1982	Japan	-	-	
	57-191247	Nov. 25, 1982	Japan	-	-	
	60-200204	Oct. 9, 1985	Japan	-	-	
	61-45201	Mar. 5, 1986	Japan	-	-	
	05-288942	Nov. 5, 1993	Japan	-	-	
	09-230048	Sep. 5, 1997	Japan	-	-	
	01-316445	Dec. 2, 1998	Japan	-	-	
	11-029335	Feb. 2, 1999	Japan	-	-	

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

"Thermal Annealing of Defects Induced by ArF Excimer Laser Irradiation in a SiO<sub>2</sub>"; Japanese Society of Applied  
Physics, Catalog No. AP 90110-02 (English Translation)

ROTHSCHILD, Mordechai, Daniel J. EHRlich and David C. SHAVER, "Excimer Laser Induced Damage in  
Fused Silica", *Microelectronic Engineering* 11, 1990, pp. 167-172.

"Temperature Dependence of the E' Center Creation in Silica Glasses", *Physica Status Solidi (b)*, vol. 147,  
No. 1, 1988, pp.k1-k4.

16821 U.S. PTO  
09/848246  
05/03/01

No Copy / No date  
No Copy / No date

Not considered  
in Parent

No date

J Hoff 10-31-03